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Docket No.: M4065.0237/P237  
(PATENT)

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

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In re Patent Application of:  
Mark Fischer et al.

Application No.: 10/768,081

Confirmation No.: 8284

Filed: February 2, 2004

Art Unit: 2815

For: DOUBLE BLANKET ION IMPLANT  
METHOD AND STRUCTURE

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Examiner: E.J. Wojciechowicz

**RESPONSE TO RESTRICTION REQUIREMENT**

MS Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

The Restriction Requirement mailed January 25, 2005 (Paper No. 0120),  
required restriction between:

Group I. Claims 56-70, drawn to a semiconductor device; and

Group II. Claims 40-55 and 71-75, drawn to a method of making a semiconductor  
device.

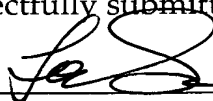
In response, Applicant hereby elects Group I, claims 56-70 for continued examination,  
without traverse.

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Dated: February 7, 2005

Respectfully submitted,

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